

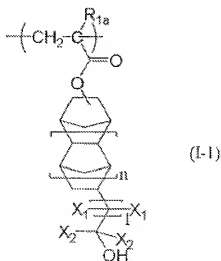
Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises from 5 to 90 mole percent of a recurring unit (I-1)
 shown by the following formula (I-1):

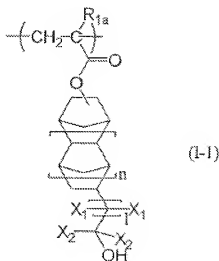


wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

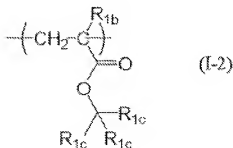
(B) a photoacid generator,

wherein the resin does not comprise an aromatic ring.

2. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (I-1) shown by the following formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (I-2) shown by the following formula (I-2):



wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator,

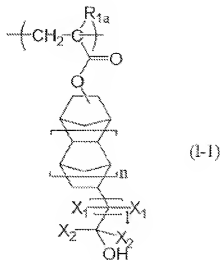
wherein the resin does not comprise an aromatic ring.

3. (Original) The radiation sensitive resin composition according to claim 2, wherein the group $-C(R_{1c})_3$ in the formula (I-2) is a 1-alkyl-1-cycloalkyl group, 2-alkyl-2-adamantyl group, (1-alkyl-1-adamantyl)alkyl group, or (1-alkyl-1-norbornyl)alkyl group.

4. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin does not contain a lactone ring.

5. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises from 5 to 90 mole percent of a recurring unit (I-1) shown by the following formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator,

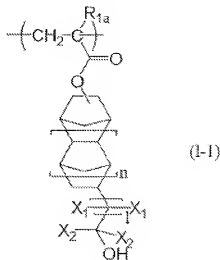
wherein the resin does not contain a lactone ring,

wherein the resin does not comprise an aromatic ring, and

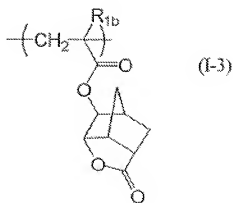
wherein the content of the recurring unit (1-1) in the resin is 40-90 mol% in 100 mol% of the total recurring units forming the resin.

6. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (I-3) shown by the following formula (I-3):



wherein R_{1b} represents a hydrogen atom or a methyl group, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

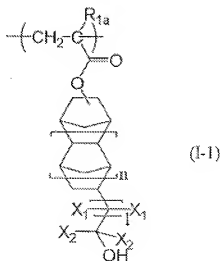
(B) a photoacid generator,

wherein the resin does not comprise an aromatic ring.

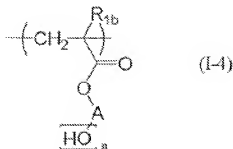
7. (Original) The radiation-sensitive resin composition according to claim 6, wherein the content of the recurring unit (1-1) in the resin is 5-25 mol% in 100 mol% of the total recurring units forming the resin.

8. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following formula (1-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, l is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-4) shown by the following formula (1-4):



wherein R_{1b} represents a hydrogen atom or a methyl group, A represents a linear or branched alkyl or alkylene group having 1-4 carbon atoms or a monovalent or divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

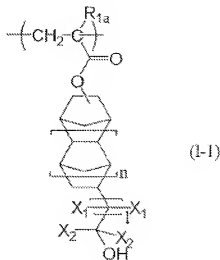
(B) a photoacid generator,

wherein the resin does not comprise an aromatic ring.

9. (Original) The radiation-sensitive resin composition according to claim 1, further comprising (C) an acid diffusion controller.

10. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (I-1) shown by the following formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid,

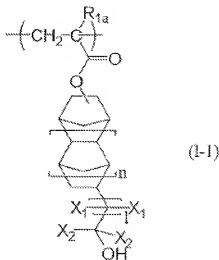
(B) a photoacid generator, and

(C) an acid diffusion controller,

wherein the resin does not comprise an aromatic ring.

11. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (I-1) shown by the following formula (I-1):



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, l is an integer of 0-5, and n is 1 or 2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

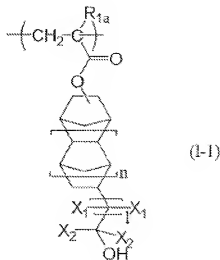
(B) a photoacid generator,

wherein the resin does not comprise an aromatic ring.

12. (Previously Presented) The radiation-sensitive resin composition according to Claim 11, wherein n is 1, l is 1, each X_1 is H and each X_2 is CF_3 .

13. (New) A radiation-sensitive resin composition comprising:

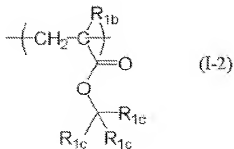
(A) a copolymer resin which comprises a recurring unit (I-1) shown by the following formula (I-1) and one or more other recurring units:



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

14. (New) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-2) shown by the following formula (1-2):



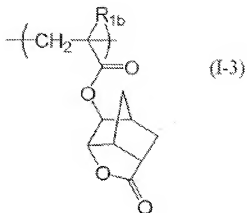
wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms.

15. (New) The radiation sensitive resin composition according to Claim 14, wherein the group $-C(R_{1c})_3$ in the formula (I-2) is an alkylcycloalkyl group.

16. (New) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-80 mol% in 100 mol% of the total recurring units forming the resin.

17. (New) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-50 mol% in 100 mol% of the total recurring units forming the resin.

18. (New) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-3) shown by the following formula (1-3):



wherein R_{1b} represents a hydrogen atom or a methyl group.

19. (New) The radiation-sensitive resin composition of Claim 13, further comprising (C) an acid diffusion controller.

20. (New) The radiation-sensitive resin composition according to Claim 13, wherein in formula (I-1) n is 1, l is 1, each X_1 is H and each X_2 is CF_3 .